

**PHOTORESIST COMPOSITION FOR FORMING CHROME BLACK MATTRESS
USED IN MANUFACTURING COLOR FILTER FOR LIQUID CRYSTAL DISPLAY**

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Abstract of KR20020076724

PURPOSE: A photoresist composition comprising polymer resin, photosensitive compound and organic solvent is provided to form a chrome black mattress used in manufacturing color filter for liquid crystal display. The resultant photoresist composition is excellent in CD uniformity, resolution, phenomenal contrast, etc. **CONSTITUTION:** The photoresist composition comprises the components of: 10-27wt.% of polymer resin, a mixture of acrylate-based resin and novolac resin in a weight ratio of 20-80 : 80-20, expressed by the formula 1(R: H or CH₃, R₂: H, alkyl, aryl or aromatic group, and n: an integer of 2-7); 3-8wt.% of photosensitive compound based on dyazide, a mixture of tetra- and tri-hydroxybenzophenone-based photosensitizers in a weight ratio of 30-70 : 70-30; 65-87wt.% of organic solvent mixing propyleneglycol monomethylether with ethyl lactate in a weight ratio of 10-50 : 90-50.

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